

**IN THE SPECIFICATION:**

Page 1, paragraph 1:

The invention relates to a vacuum plasma generator for feeding a plasma discharge for the purpose of treatment of workpieces in a vacuum chamber according to ~~claim 1~~, as well as ~~to a method~~ to the claims, as well as a method for the production of a layer by reactive deposition out of a plasma ~~according to claim 12~~.

Page 4, paragraph 3:

This problem is solved according to the invention through a vacuum plasma generator ~~according to claim 1~~ and through a method ~~according to claim 12~~. The dependent claims define further advantageous embodiments.

Page 6, paragraph 3: after the word "configuration", add the following new paragraph:

--The various features of novelty which characterize the invention are pointed out with particularity in the claims annexed to and forming a part of this disclosure, and are entirely based on the priority application, CH 458/02, filed March 15, 2002 in Switzerland.--